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# United States Patent [19]

Kokado et al.

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[54] PROCESS FOR PRODUCING THIN FILMS

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[ * ] Notice: The portion of the term of this patent subsequent to Jun. 16, 2009 has been disclaimed.

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**Related U.S. Application Data**

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Dec. 17, 1988 [JP] Japan ..... 63-317627
May 12, 1989 [JP] Japan ..... 1-117481

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[52] **U.S. Cl.** ..... **204/180.2**; 204/181.7; 205/317; 205/323; 430/127; 556/143; 556/144; 252/352

[58] **Field of Search** ..... 204/180.2, 72, 181.7; 430/127; 556/143, 144; 252/352; 205/323, 317

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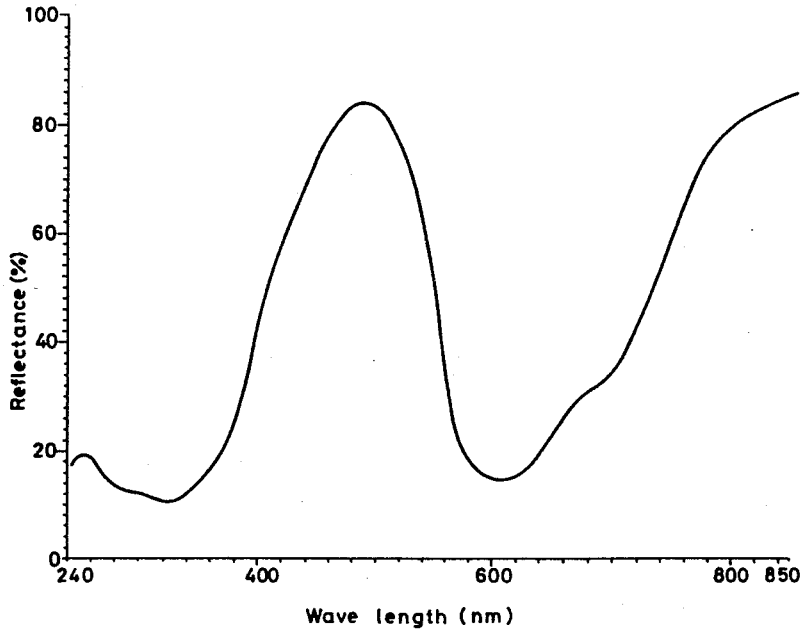
[57] **ABSTRACT**

A process for producing a thin film comprising electrotreating a dispersion or solution obtained by dispersing or dissolving a hydrophobic substance powder in an aqueous medium with a surfactant having a HLB value of 10.0 to 20.0, under conditions for forming a thin film of the hydrophobic substance on a cathode. The thin film of a hydrophobic substance can be formed on base metals such as aluminum, which can be applied to photosensitive materials and the like.

**18 Claims, 9 Drawing Sheets**